

Advanced Metrology for Atypical Surfaces

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Acknowledgements:

Jim Kirsch

Weapons Science Directorate

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Command

Advantages of subaperture stitching

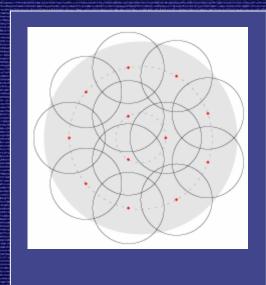


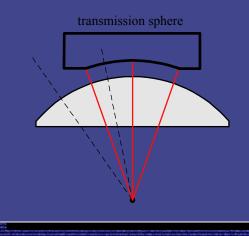
- Use of smaller interferometers
 - Shorter air path (concaves) (use long radius diverger)
 - Smaller transmission optics (convex)
- Higher lateral resolution
 - Subaperture has the full interferometer resolution, so the stitched result can have more than that
- Calibration of systematic errors
 - Part motion allows reference wave and other calibrations
- Avoid null optics for aspheric testing
 - Again, the subaperture has the interferometer capability, so the stitched result can have more
 - Thus a high enough magnification with enough subapertures can non-null test an asphere

Stitching background and motivation



- Background subaperture stitching is not new
 - Low-order polynomial fit to nonoverlapped subapertures
 - Microscope pair-wise stitching
 - Zonal (annular subaperture) asphere testing
 - Translation along aspheric caustic to match local radius
 - Large, high-resolution plano optics
 - Simultaneous optimization of DC and tilt of all subapertures



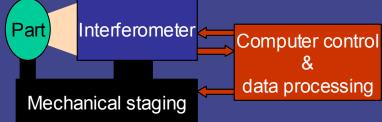


The SSI System



- 4" or 6" Zygo GPI Interferometer
- 6-axis computer controlled workstation
 - Engineered in cooperation with Schneider Opticmachines
- QED patented techniques and advanced software
 - Motion control
 - Interferometer control
 - Stitching algorithms
 - Automation



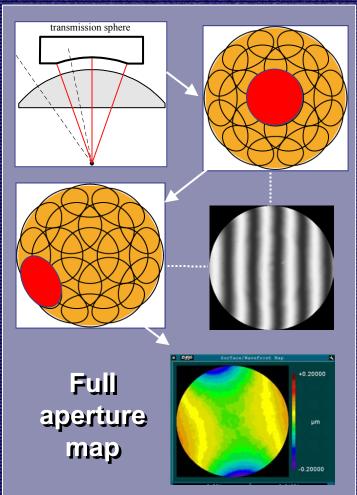


Innovative Metrology: SSI Subaperture Stitching Interferometer



- Full aperture measurement of large NA & CA parts
- Completely Automatic
 - Auto-Positioning, nulling, & radius testing
- Intuitive & Easy to Operate
 - Reference wave, distortion, pixel scale calibration





SSI measurement example



Aperture – 148.34 mm (5.84")

Radius – 82.55 mm (3.25")

CT - 3.04 mm (0.12")

Sag - 50.39 mm (1.984")

Objective - Zygo 4" f/1.5

Subaperture = 55.1 mm

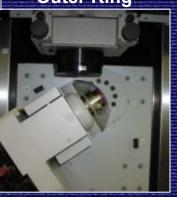
Required 25 subapertures -

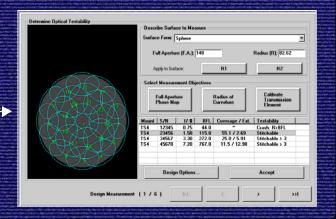
(4 center, 9 inner, 12 outer)

Inner Ring



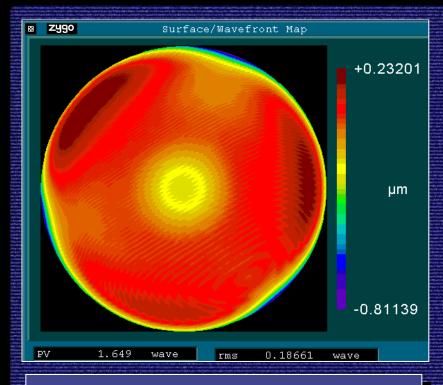






The Stitched Result





Radius: 82.6 mm

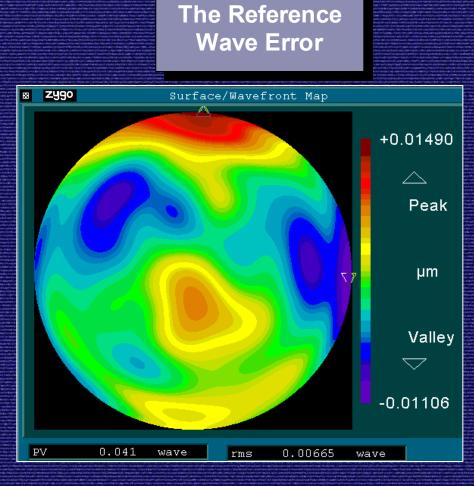
Surface:

PV – 1.649 λ (@ 633nm)

Rms $- 0.187 \lambda (@ 633nm)$

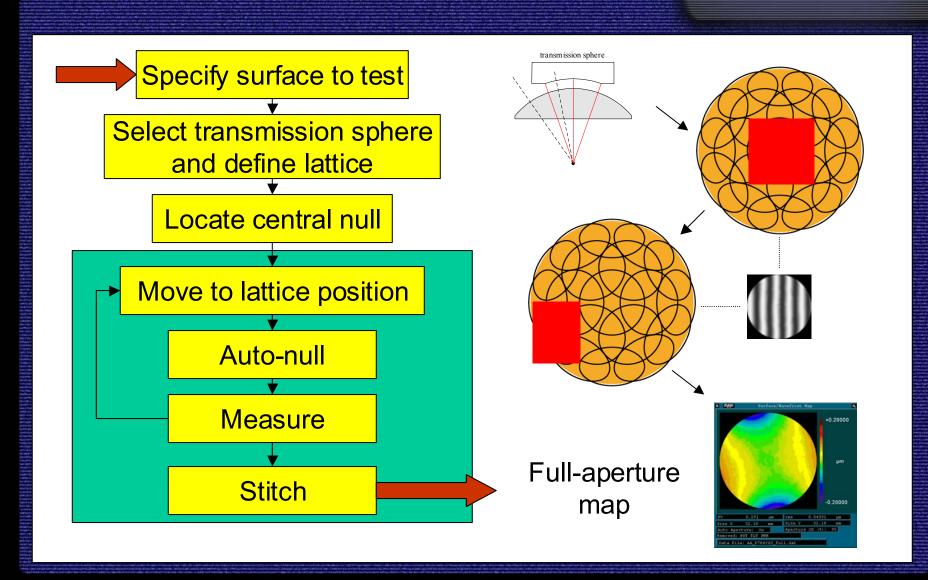
Total measurement time:

12 minutes!!



SSI measurement process





Stitching algorithm



- Minimizes mismatch in overlap regions by adding an optimal amount of error compensation
 - Free compensators: vary in each subaperture
 - Traditional alignment errors: piston, tilt, power
 - ❖ But other errors can be included, e.g. translation, orientation
 - Interlocked compensators: same in each subaperture
 - Reference wave error (as a Zernike polynomial series)
 - ❖ Geometric distortions of viewing system
 - Does not require separate calibration procedure to determine and separate systematic errors from stitched results!

$$F_j(x,y) = f_j(x,y) + DC_j + Xtilt_j x + Ytilt_j y + Power_j (x^2 + y^2)$$

$$F_{j}(x,y) = f_{j}(x,y) + \left[\sum_{k} a_{jk} g_{jk}(x,y)\right] + \left[\sum_{i} \alpha_{i} G_{ji}(x,y)\right]$$

Example of stitchingcomputed reference wave



Reference wave compensation

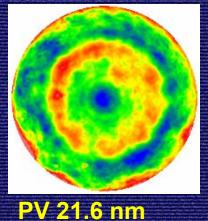
OFF

full aperture rms mismatch

PV 24.2 nm PV 12.2 nm

reference wave

ON

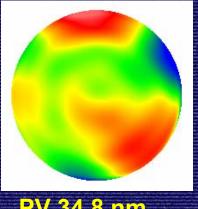


rms 3.10 nm

rms 3.71 nm

PV 6.64 nm

rms 4.56 nm



PV 6.64 nm PV 34.8 nm rms 1.05 nm rms 4.34 nm

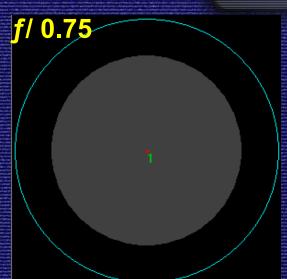
Metrology performance – stitched vs. full-aperture

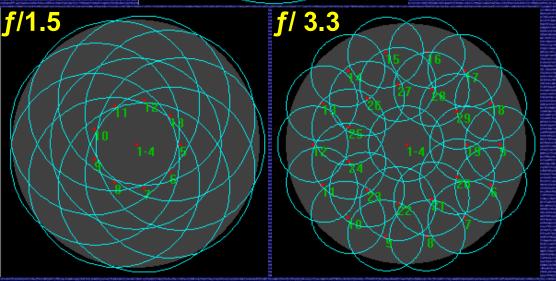


Comparison of stitched and full-aperture measurements



Ø: 38 mm R: 41.23 mm R/ 1.09

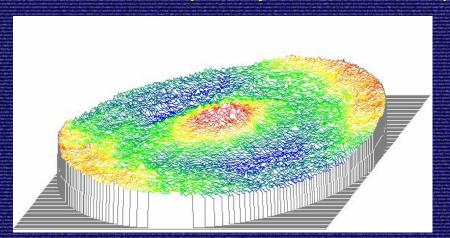




Full-aperture measurement using TS 4" f/ 0.75

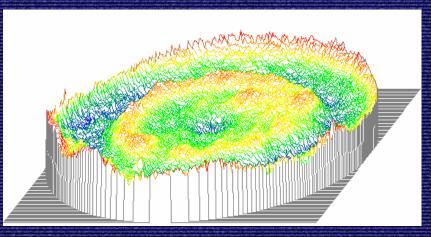


reference wave (two-sphere calibrated)



PV: 14.7 nm rms 2.19 nm

test surface



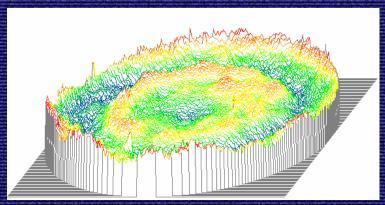
PV: 36.6 nm rms 3.72 nm

Stitched measurement using TS 4" f/ 1.5

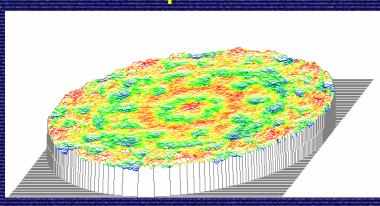




Difference from full aperture measurement

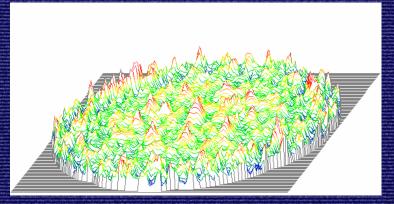


PV: 33.0 nm rms 3.64 nm



PV: 6.68 nm rms 0.66 nm

rms mismatch



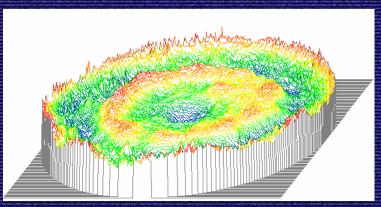
PV: 3.46 nm rms 1.17 nm

Stitched measurement using TS 4" f/ 3.3

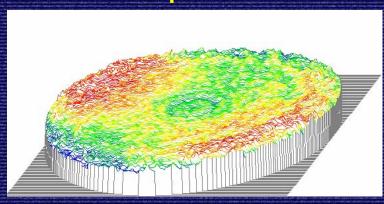




Difference from full aperture measurement

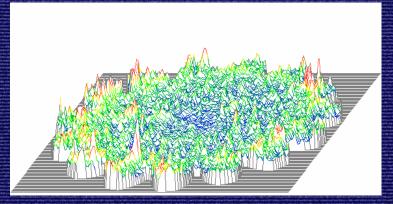


PV: 28.9 nm rms 3.18 nm



PV: 10.4 nm rms 1.32 nm

rms mismatch

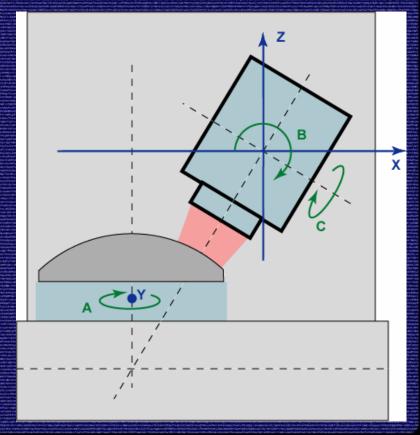


PV: 4.51 nm rms 1.05 nm

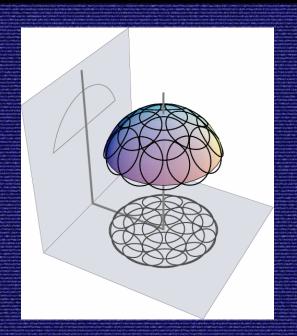
Stitching merits for large mirrors



- Boosted testable aperture sizes (i.e. cost-effective reference optics)
- Boosted testable aspheric departure (can alleviate need for nulls)
- Boosted accuracy (from thorough, automated calibration of reference wave, distortion, retrace, etc.)
- Boosted resolution
- Reduced non-common air path for long-radius concaves
- Dominant uncertainty well matched to adaptive mirrors







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